

TABLE OF CONTENTS

	Page
Acknowledgements	iii
Abstract in English	iv
Abstract in Thai	vi
List of Tables	x
List of Illustrations	xi
List of Publications and Presentations	xv
Chapter 1 Introduction	1
Chapter 2 Principle of Rf Multicusp Ion Source	
2.1 Physics of Ion Source	5
2.2 Inductive Discharge	8
2.3 Multicusp Field	10
2.4 Beam Extraction	13
2.5 A 13.56 MHz Multicusp Ion Source	17
Chapter 3 Plasma Simulations and Diagnostics	
3.1 Plasma Simulation : XOOPIC	23
3.2 Optical Emission Spectroscopy (OES)	30
3.3 Rf Compensated Langmuir Probe	33
3.4 OES and L-probe Setup and Results	35
Chapter 4 Characteristics of Argon Beam	
4.1 Experimental Arrangement	44
4.2 3-electrode Extracting System	45

4.3 Scanning Wire Beam Profile Monitor	49
4.4 Beam Emittance Measurement	53
4.5 Beam Energy Spread Measurement	58
4.6 FIB System: Conceptual Design Study	62
Chapter 5 Conclusions	68
References	70
Appendices	
Appendix A The Child-Langmuir law	74
Appendix B	75
B1 Fortran code to calculate B-field in multicusp ion source	
B2 Data file for Argon plasma simulation: XOOPIC	
Appendix C The phase ellipse relation	79
Appendix D Papers by author	80
D1 Paper I: A 13.56 MHz multicusp ion source for high intensity Ar Beam, <i>Rev. Sci. Instrum.</i> 71(2) 1181 2000.	
D2 Paper II: Plasma emission in vacuum arc and RF-discharge plasma source, <i>Rev. Sci. Instrum.</i> 73(2) 754 2002.	
D3 Paper III: Characteristics of a 13.56 MHz radiofrequency driven multicusp ion source, submitted for publication in <i>Plasma Sources Science and Technology.</i>	
VITA	103

LIST OF TABLES

Table		Page
3.1	Data of transition probabilities: A , statistical weights: g and energies: E of upper levels	43
4.1	Comparison of gas and ionization mean free path at various Argon pressures	47
4.2	α ratio as functions of V_b and I_b from a 100 micron beam	63

LIST OF ILLUSTRATIONS

Figure	Page
2.1 Ionization, excitation and elastic scattering cross-sections for electrons in Argon gas	7
2.2 The equivalent circuit of a plasma in the inductive discharge	8
2.3 Rf field induced by an antenna propagates through a plasma with skin depth δ_p	9
2.4 Comparison of the calculated cusp field and field strength using MAGNUS code for Sm-Co ₅ and Nd-Fe-B magnets	13
2.5 Schematic diagram of ion extraction from a plasma source	14
2.6 The Paschen curve of air dielectric strength range at varied pressure	16
2.7 Rf-multicusp ion source developed for high-intensity Ar beam production operates at 13.56 MHz	17
2.8 20 rows of Nd-Fe-B permanent magnets were installed around ion source chamber to produce multicusp field	18
2.9 A 2 turns, 6 cm in diameter quartz antenna was installed on the back flange supplies rf power to the plasma inside the source volume	19
2.10 The matching network working at 13.56 MHz includes a 10:1 transformer, a variable capacitor and an inductor in a shielded box	20
2.11 Measured radial B field strength of 0.18 T was found maximum at the source inner wall ($r = 0$)	21
2.12 Measured multicusp field for half circle at the source inner wall:	21

	starting between 1 st magnets pair and end between 10 th magnets pair	
2.13	A sample of Argon plasma confinement result seen inside the source chamber: 50 watts rf power, 10 mTorr Argon pressure	22
3.1	Schematic diagram of the simulation model with cylindrical shaped boundary 10 cm diam and 9 cm long. The z-axis is taken as the symmetry axis	26
3.2	XOOPIC simulation results in r-z space at 10 mTorr base pressure:	27
	(a) the calculated particles density against time; (b) the magnetic field inside the source volume	
	(c) profile of the electron density (d) profile of the ion density;	28
	(e) electron distribution	
	(f) ion distribution; (g) T_e profiles against time. All data are taken at 373 ns revolution time	29
3.3	OES measurement setup using Ocean Optics S2000 spectrometer	33
3.4	Rf-compensated Langmuir probe schematic	35
3.5	Photo of a self-built rf-compensated Langmuir probe. The probe tip is set to 90 degree for radial profile measurement within ± 4.5 cm range	35
3.6	OES and Langmuir probe measurements setup	37
3.7	a) OES spectrum of Argon plasma at 2 mTorr 200 watts rf power	37
	b) line intensity as a function of rf power at 8 mTorr Argon pressure	38
	c) line intensity as a function of argon gas pressure at 400 watts rf power	38
3.8	Mode jump in N ₂ discharges as the discharge mechanism changes from capacitive to inductive: at 8 mTorr	40

3.9	A typical probe I-V curve from Argon plasma at $P_{rf} = 200$ W	41
3.10	Density profile in the radial direction 1 cm from the antenna	41
3.11	Decreasing of electron temperature with log of pressure measured by Langmuir probe (top) and OES (bottom)	43
4.1	System setup consisted of ion source, experiment chamber, and window	44
4.2	Samples of KOBRA simulation of 9 keV Ar beam from a 3 electrode extraction system at different values of perveance a) $0.3P_0$, b) $0.45P_0$ and c) $1.0P_0$. The grids were biased with 9, -1 and 0 kV, respectively	46
4.3	Pressure dependencies of the extracted Ar beam from this setup	47
4.4	Ar current extracted from the ion source at different rf power at a base pressure of 8 mTorr	49
4.5	Show 50 micron W wire as a beam sensor on scanning wire BPM	50
4.6	Plateau of the bias voltages plot as a function of Ar beam energy	51
4.7	A measured beam profile as a function of the extracting voltage at 3 cm from the ground electrode using the scanning wire BPM	52
4.8	The beam profile of the 12 keV focused Ar beam at different locations	53
4.9	A phase ellipse of a beam in phase space	54
4.10	Emittance measurement setup using quadrupole scan method a) schematic diagram b) a quadrupole magnet c) a 16x16 multiwire BPM	56
4.11	A plot of polynomial fitting between quadrupole current vs beam width	57
4.12	Phase-space diagram of 9 keV Ar beam results the rms beam emittance of 32 ± 4 mm mrad	58

4.13	The RFA developed for beam energy spread measurement	59
	a) schematic diagram b) actual RFA with a ground shield	
4.14	Energy spread of Ar beam at 0.5 to 4 keV energy	61
4.15	Effects of with and without 0.1 μF bypassing capacitor on energy spread	61
4.16	Modeling of the 100 micron beam extraction with its emittance. Ar beam current is extracted with 1 kV for the case of a) 1 μA , b) 10 μA , c) 100 μA and d) 1000 μA	64
4.17	Effects of different lens voltage on the Einzel lens with 6 mm aperture a) 0.5 kV b) 0.8 kV and c) 1 kV	66
4.18	Beam emittance of a 1 keV Ar beam after the 0.8 kV biased Einzel lens	67

LIST OF PUBLICATIONS AND PRESENTATIONS

Publications

1. D. Boonyawan, N. Chirapatpimol, N. Sanguansak, and T. Vilaithong 2000. A 13.56 MHz multicusp ion source for high intensity Ar beam, *Rev. Sci. Instrum.* 71(2) 1181.
2. D. Boonyawan, S. Davidov, B. Yotsombat, N. Chirapatpimol, and T. Vilaithong 2002 Plasma emission in vacuum arc and RF-discharge plasma source, *Rev. Sci. Instrum.* 73(2) 754.
3. D. Boonyawan, N. Chirapatpimol, and T. Vilaithong: *Characteristics of a 13.56 MHz radiofrequency driven multicusp ion source*, submitted for publication in *Plasma Sources Science and Technology*.

Presentations

1. D. Korzec, D. Boonyawan, J. Engemann, *Microwave slot antenna type ultraviolet light source for fluid treatment*, The 8th International Symposium on the Science and Technology of Light Sources LS-8, Greifswald, Germany; 30. Aug. - 3. Sept. 1998.
2. D. Boonyawan, N. Chirapatpimol, and T. Vilaithong, *A 13.56 MHz multicusp ion source for high intensity Ar beam*, The 8th International Conference on Ion Sources, Kyoto, Japan, 6-10 Sep 1999.
3. D. Boonyawan, S. Davidov, B. Yotsombat, N. Chirapatpimol, and T. Vilaithong, *Plasma emission in vacuum arc and RF-discharge plasma source*, The 9th International Conference on Ion Sources, Oakland CA, USA, 3-7 Sep 2001.

4. D. Boonyawan, N. Tondee, P. Chaiwan, S. Amkaew, M. Rhodes and T.Vilaithong, *Beam diagnostics of Radiofrequency driven multicusp ion source*, International Workshop on Particle Beams & Plasma Interaction on Materials, Chiang Mai, THAILAND, 31 Jan-1 Feb 2002.

มหาวิทยาลัยเชียงใหม่
Chiang Mai University